

4~12wafers Fully automatic RCA cleaning machine

Model: SA-RCA-48LS

SA-RCA-48LS is crafted with premium materials to endure acidic corrosive working environments. Adopting modular tank design and advanced automatic manipulators, it delivers stable and consistent cleaning performance for semiconductor wafers. Equipped with high-end control components and compatible with MES systems, it realizes intelligent operation. With reliable leakage prevention and optimized ventilation design, it ensures safe, efficient and eco-friendly operation, perfectly meeting the rigorous cleaning demands of the semiconductor industry.



Feature

- Long-time Acidic Corrosion Resistant
- Double-layer Leak-proof
- Customize for Manual and Fully Automatic
- Support MES system
- ISO9001 Quality Assurance

Application

- Wafer Front-End Cleaning
- Photolithography Cleaning
- Etch Post-Cleaning
- Thin Film Cleaning
- Back-End Packaging

Specifications:

Parameter	Descriptions
Wafer Size	4"/5"/6"/8"/12"
Cleaning Capacity	4"~8":25pieces2baskets/batch 12":25pieces/batch
Control Part	PLC and HMI